


RSC-NRF Rates effective July 1st 2015

All rates are user rates, additional charge applied for staff operation of tools
For external rates, see the notes section at bottom.

INSTRUMENT RESOURCE		INTERNAL RATES FY2015	NOTE	Training scheduled (discounted)	Training ad-hoc (full price)
Hourly Rate Tools		(\$/15 min)		(\$/user)	(\$/user)
Acid Bench (heated baths) - JST	6.00			17.00	37.00
Acid Bench (general use) - left	6.00			training is part of orientation	
Acid Bench (RCA) - Amerimade	6.00		1	33.00	74.00
Asher - Anatech Barrel SCE600	11.00			20.00	47.00
Bruker Optical Profilometer	6.00			66.00	148.00
Dicing Saw - ADT	10.00			115.00	270.00
Dicing Saw - ADT - Blade changing training				25.00	90.00
E-beam evaproator - PVD	12.00		2	82.00	196.00
E-Beam Lithography - Raith 150 (rate includes development of pattern)	12.50			229.00	NA 4 day training
Ion Beam Lithography (FIB) with Multi Species - Raith ionLINE	17.00			229.00	NA 4 day training
Ellipsometer, J.A. Woolam	5.00			32.00	70.00
Flexus 2320 - wafer bow measurement	5.00			16.00	35.00
Four Point Probe - Veeco FPP-5000	0.00			0.00	0.00
Furnace Tube, Thermcraft, General Hot Process	5.00			32.00	70.00
Furnace Tube, Tystar #1 Wet and dry Ox	6.00			33.00	74.00
Furnace Tube, Tystar #2 dry Ox and Annealing	6.00			33.00	74.00
Furnace Tube, Tystar #3 LPDCV Nitride (staff run)	not in service				
Furnace Tube, Tystar #4 Poly sil and doping (staff run)	not in service				
Hall Effect Electronic Measurement - Lakeshore 7507	5.00			32.00	70.00
HMDS hotplate	0.00			Training performed with spinners	
Lapper/Polisher	0.00			13.00	25.00
Mask Aligner - EVG Model 620 w/BSA (rate include development of pattern)	11.00			80.00	188.00
Mask Aligner - Karl Suss MA6 (rate includes development of pattern)	11.00			60.00	141.00
Maskless Laser Writer - Heidelberg DWL-66 (rate includes development of pattern)	12.00			82.00	196.00
Micro Raman - Horiba Aramis	11.00			60.00	141.00
MOCVD for GaN, ZnO, Si, C - SMI Nano-H CVD	7.00		3	TBD	TBD
Nikon cleanroom microscope with digital image capture	0.00			13.00	25.00
Oven, Image Reversal/HMDS - YES	8.00			Training performed with spinners	
PECVD SiNx, SiO2, Amorphous Si - STS 310PC	12.00			41.00	98.00
Photospectrometer - Filmetrics F40	5.00			16.00	35.00
Probe station, 5 pt probe	0.00			13.00	25.00
Profilometer - Dektak 150	11.00			40.00	94.00
Profilometer - Tencor Alpha-Step-500	5.00			16.00	35.00
RIE, Deep Si - STS	12.00			103.00	245.00
RIE/ICP - Unaxis SLR	12.00			41.00	98.00
RIE/ICP - Trion	12.00			41.00	98.00

RTA - Steag 100CS RTP	11.00
RTA - Solaris 150	11.00
SEM - FEI Nova NanoSEM 430 with CL	15.00
SEM - FEI Nova NanoSEM 430 with CL - CL training for above	
SEM - JEOL 5700 CarryScope	11.00
Solvent bench 1, lift off	0.00
Solvent bench 2, lift off	0.00
Spin Coater - Headway, E-Beam Bay (rate includes soft/hard bake & basic litho chemicals)	8.00
Spin Coater - Laurell, E-Beam Bay (rate includes soft/hard bake & basic litho chemicals)	8.00
Spin Coater - Laurell, Litho Bay (rate includes soft/hard bake & basic litho chemicals)	8.00
Spin Coater - Headway, Litho Bay (rate includes soft/hard bake & basic litho chemicals)	8.00
Spin Coater - Suss, Delta 80 (rate includes soft/hard bake & basic litho chemicals)	11.00
Sputter Deposition - KJL CMS-18 Multi-Source	12.00
Wafer Bonder, EVG 501	8.00
Wire Bonder, Gold Ball	8.00
Wire Bonder, Wedge (staff run; there are additional charges for staff time)	8.00
Per Run Rate Tools	(\$/run)
ALD - Cambridge Nanotec Fiji	90.00
Critical Point Dryer (includes dedicated acid bench and CPD tool)	60.00
SCS Parylene Coater	25.00
Other Charges	
Additional Analysis ,Reporting, Sample Prep- Technician Time (per hour)	50.00
Cleanroom entry fee (per day)	15.00
Technician time (per hour)	50.00

20.00	47.00
40.00	94.00
90.00	220.00
90.00	220.00
40.00	94.00
Training performed with spinners	
training is part of orientation	
54.00	123.00
all spinners trained together (rates above)	
all spinners trained together (rates above)	
all spinners trained together (rates above)	
all spinners trained together (rates above)	
62.00	147.00
36.00	82.00
107.00	285.00
staff run	
55.00	140.00
85.00	175.00
52.00	113.00

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Notes:

- \$35 consumable surcharge per use for RCA bath fills
- Consumable surcharge (per Å) for the following precious metals: Au, Pt, Pd, Ir, Ru, Ag
All other materials included in hourly rate.
- Consumable surcharge calculated based on usage
- Consumable surcharge \$15 to cover acids, alcohols and CO2
- Run includes up to 7gm of parylene. Additional Parylene can be purchased for thicker films.

All tools are billed based on 15 min increments unless otherwise noted

External Rates:

Internal UF Customers pay Base Rates
Other Academic Institutions, Government labs, and UF-Affiliated Companies pay 1.5 x Base Rates
Non-Affiliated Companies pay 2.0 x Base Rates, daily cleanroom fee is \$20
The external non-affiliate rate for the FEI SEM and the Horiba micro-Raman are \$50/15min
*** Refer to External Rate Policy for more information and exclusions

NRF Store consumables	price each
100mm Si wafer - Prime grade	22.18
100mm Si wafer - Test Grade	12.18
50mm Si wafer - test grade (n-type)	10.00
50mm Si wafer - test grade (p-type)	10.00
50mm Sapphire wafer - single side polished	31.81
4" mask blank - sodalime glass, Cr (includes mask holder)	19.42
4" mask blank - sodalime glass, FeO (includes mask holder)	42.29
4" mask blank - quartz glass, Cr (includes mask holder)	85.25
5" mask blank - sodalime glass, Cr (includes mask holder)	26.11
5" mask blank - sodalime glass, FeO (includes mask holder)	49.50
5" mask blank - quartz glass, Cr (includes mask holder)	100.50
2" square acrylic sample box (sold as a 10 pack)	2.50
50mm single wafer shipper - epak (sold as singles)	2.75
75mm single wafer shipper - epak (sold as singles)	3.75
100mm single wafer shipper - epak (sold as singles)	4.80
100mm graphene support wafer 300nm SiO2/Si (includes single wafer shipper)	38.74